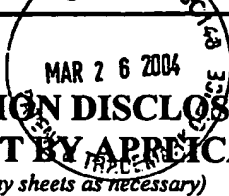
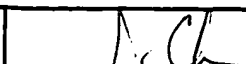


Substitute for form 1449A/PTO			<div style="text-align: center;">  </div>		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)			Complete if Known		
			Application Number	10/729,452	
			Filing Date	December 4, 2003	
			First Named Inventor	Robert David ALLEN et al.	
			Art Unit	1756	
Examiner Name	Unassigned				
Attorney Docket Number	ARC920030104US1				
Sheet	1	of	1		

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Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
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	AC	5,919,597	7/6/99	Sinta et al.	430	270.1	
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	AJ	WO 02/079287	10/10/02	PCT			
	AK	WO 03/040827	5/15/03	PCT			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS							
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					T
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Examiner Signature		Date Considered	6/20/06
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet

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Complete if Known

Application Number	10/729,452
Filing Date	December 4, 2003
First Named Inventor	Robert David ALLEN et al.
Art Unit	1756
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Attorney Docket Number	ARC920030104US1

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Examiner Signature	<i>J. L. R.</i>	Date Considered	6/2006
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.